

CVD of PtRh WITH GOOD ADHESION AND MORPHOLOGY

Abstract of the Disclosure

5 A method and system for performing metal-organic chemical vapor deposition
(MOCVD). The method introduces a metal-organic compound into the CVD chamber
in the presence of a first reactant selected to have a reducing chemistry and then,
subsequently, a second reactant selected to have an oxidizing chemistry. The reducing
chemistry results in deposition of metal species having a reduced surface mobility
creating more uniform coverage and better adhesion. The oxidizing species results in
10 deposition of metal species having a greater surface mobility leading to greater surface
agglomeration and faster growth. By alternating the two reacts, faster growth is
achieved and uniformity of the metal structure is enhanced.

15
R:\DOCS\JQHJQH-1007.DOC
040501